

Received
Sept 26 1995
Group 1507

Case 2 68520 1507

RESPONSE UNDER 37C.F.R. 1.116
-EXPEDITED PROCEDURE-
EXAMINING GROUP 1507



In the United States Patent and Trademark Office

In re Application of:

Neil F. Haley, et al

RADIATION-SENSITIVE
COMPOSITION CONTAINING A
RESOLE RESIN, A NOVOLAC
RESIN, AN INFRARED ABSORB-
ER AND A TRIAZINE AND USE
THEREOF IN LITHOGRAPHIC
PRINTING PLATES

Serial No. 212,434

Filed 14 March 1994

Honorable Assistant Commissioner For Patents
Washington, D.C. 20231

Sir:

AMENDMENT AFTER FINAL REJECTION

In response to the Office Action of August 7,
1995, please amend the above-identified application as
follows:

In the Claims:

Please amend claim 1 as follows:

1. (Amended) A radiation-sensitive
composition useful for the preparation of an imaging
layer of a lithographic printing plate that is
sensitive to both ultraviolet and infrared radiation
and capable of functioning in either a positive-working
or negative-working manner; said radiation-sensitive
composition comprising (1) a resole resin, (2) a
novolac resin, (3) a haloalkyl-substituted S-triazine,
and (4) an infrared absorber in amounts such that the
solubility of said imaging layer in aqueous alkaline
developing solution is reduced in exposed areas and
increased in unexposed areas by the steps of imagewise
exposure to activating radiation and heating.

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Group Art Unit: 1507

Examiner: L. Weiner

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20231.

Alfred P. Lorenzo

Name

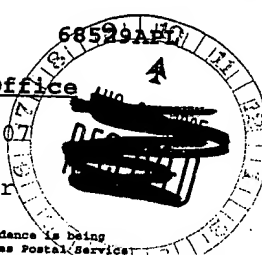
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Reg. No.

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Date of Signature

AUGUST 21, 1995



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